



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Gurtej Singh Sandhu et al.

Title: METHOD TO REDUCE FIXED CHARGE IN CVD OZONE DEPOSITED FILMS

Docket No.: 303.573US1

Filed: April 22, 1996

Examiner: Erik Kielin

Serial No.: 08/636,069

Due Date: April 23, 2001

Group Art Unit: 2813

B x AF

Commissioner for Patents
Washington, D.C. 20231

We are transmitting herewith the following attached items (as indicated with an "X"):

- X A return postcard.
- X An Amendment and Response (15 Pages).
- X A Clean Version of Pending Claims (9 pages)

Please consider this a **PETITION FOR EXTENSION OF TIME** for sufficient number of months to enter these papers and please charge any additional required fees or credit overpayment to Deposit Account No. 19-0743.

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.
P.O. Box 2938, Minneapolis, MN 55402 (612-373-6900)

By: Leoniede M. Brennan 4/23/01
Atty: Leoniede M. Brennan
Reg. No. 35,832

CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail, in an envelope addressed to: Box AF, Commissioner for Patents, Washington, D.C. 20231, on this 23 day of April, 2001.

Name

Tina Pugh

Signature

Leoniede M. Brennan

Customer Number 21186

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.
(GENERAL)

P.O. Box 2938, Minneapolis, MN 55402 (612-373-6900)

AF/GAU 2812
Initial Review
BOX AF
RECEIVED
APR 30 2001
2800 MAIL ROOM
#25/9
5-1-01
J. K.



EXPEDITED PROCEDURE - EXAMINING GROUP 2813

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Gurtej Singh Sandhu, et al. Examiner: Erik Kielin
Serial No.: 08/636,069 Group Art Unit: 2813
Filed: April 22, 1996 Docket: 303.573US1
Title: METHOD TO REDUCE FIXED CHARGE IN CVD OZONE DEPOSITED FILMS

AMENDMENT AND RESPONSE UNDER 37 C.F.R. § 1.116

Box AF
Commissioner for Patents
Washington, D.C. 20231

RECEIVED
APR 30 2001
TO 2800 MAIL ROOM

Applicant has reviewed the Final Office Action mailed on January 23, 2001. Please amend the above-identified patent application as follows.

IN THE CLAIMS

Please substitute the claim set in the appendix entitled Clean Version of Pending Claims for the previously pending claim set. Specific amendments to individual claims are detailed in the following marked up set of claims.

Please amend the claims as follows:

1. (Amended) A chemical vapor deposition (CVD) process for depositing borophosphosilicate glass films on a substrate surface, the process comprising:
 - disposing the substrate within a chemical vapor deposition reaction chamber;
 - heating the substrate to a temperature within a range of at least 480°C to about 700°C;
 - introducing a gas volume of SiO₂ precursors into the chamber;
 - admitting a gas volume of ozone into the chamber;
 - admitting a dopant source for phosphorus into the chamber;
 - admitting a dopant source for boron into the chamber; and
 - exposing a reaction volume of gases located above the substrate surface within a chemically reactive distance of the substrate to a high intensity light

OKAY TO ENTER ER 3/17/03/RES 5/23/01
DO NOT ENTER ER 5/3/01
Page No. 23